

CYRUS

Dry Solution to Toxic Abatement



System Description

Cyrus is a dry adsorption system that removes various gas phase contaminants from semiconductor effluent gas streams. Primarily used in point-of-use (POU) applications, Cyrus utilizes proprietary, passive, adsorptive materials that remove and concentrate dangerous and highly toxic compounds such as Arsine (AsH₃), Phosphine (PH₃), and Germane (GeH₄). This system can also remove organic compounds and high molecular weight VOC's. Different media mixtures can be provided for adsorbing acid gases and ammonia as well.

Cyrus is available in multiple configurations and sizes. Dual alternating chambers and multistages are available. Sensors monitor pressure drop, temperature, and canister capacity for breakthrough.

Cyrus can be custom-engineered to handle specific processes. In addition, Cyrus can be utilized in conjunction with other Enviro-Matrix systems as a pre- or post-treatment stage.

Advantages

- Abatement to below TLV
- Very high capacities
- Compact and reliable
- Proven performance
- Concentrates toxics
- Small footprint
- Single and dual configurations
- Safe passive design
- Automatic inert purge
- Bed saturation detectors available
- Dual canister designs available

Cyrus with Cabinet Door Open

ENVIRO-MATRIX Cyrus Adsorption Abatement Process

Control of Toxic Gases

Specifications

Outlet Connection: 1.5" KF 40

Inlet Connection: 1.5" KF 40

Max. Inlet Gas Flow: up to 300 slm

Typical Gas Flow Rate: 100-150 slm N2

Maximum Contaminant Flow: 4-5% by volume in mixture

Canister Dimensions: 12" O.D. x 70" Tall

Enclosure (Single): 32" L x 32" W x 92" H

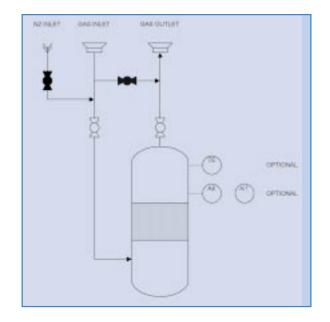
Cabinet Exhaust Requirement: 300 cfm

Applications Gases Treated

Ion Implant BF₃, ASH₃, PH₃

Metal Etch BCl₃, Cl₂, HF

MOCVD ASH₃, PH₃, TMGa



East Coast: 1-800-645-9846 • 631-694-9555 West Coast: 1-866-519-3603 • 503-419-2200 Fax: 631-694-9412 www.enviro-matrix.com Fax: 503-284-4296 Email: info@enviro-matrix.com